

**AMENDMENTS TO THE SPECIFICATION**

Please amend the paragraph starting at page 8, line 28, as follows:

Hereinafter, a method of fabricating the liquid crystal display device with an ink-jet color filter shown in Fig. 3B will be described with reference to Fig. 4A to Fig. 4F. Referring to Fig. 4A, the gate electrode 32 and the gate insulation film 34 are formed ~~et++n~~ on the transparent film 30. The gate electrode 32 is provided along with the gate line (not shown) by depositing a metal material such as Mo, Ta, or Al alloy, etc. on the transparent substrate 30 using the sputtering technique and thereafter patterning the metal material using photolithography. The gate insulation film 34 is provided by depositing an insulating material such as SiNx or SiOx, etc. over the entire surface of the transparent substrate 30 using the CVD (plasma chemical vapor deposition) technique.